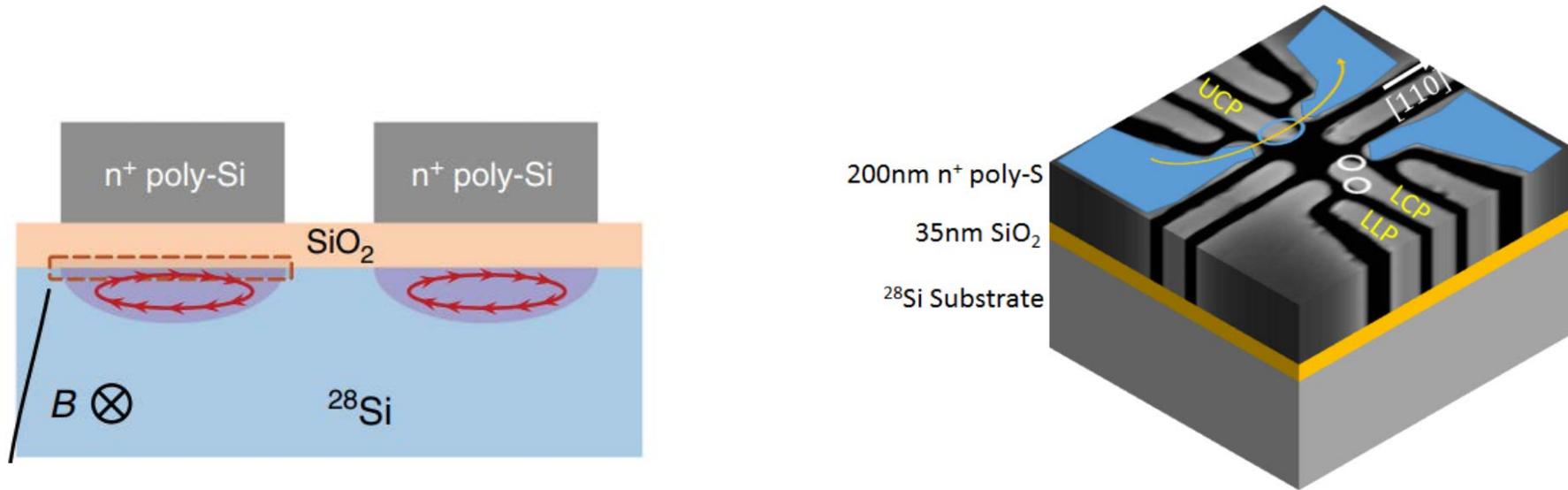


# A Silicon Metal-Oxide Semiconductor Electron Spin-Orbit Qubit



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Jock et al., Nature Comm. **9**, 1768 (2018)

# Outline

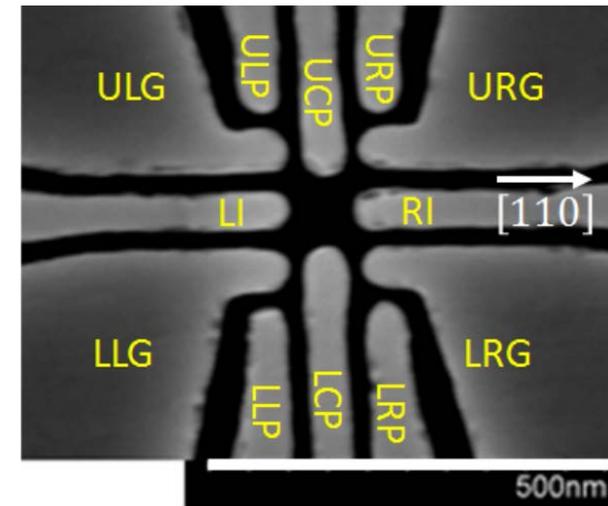
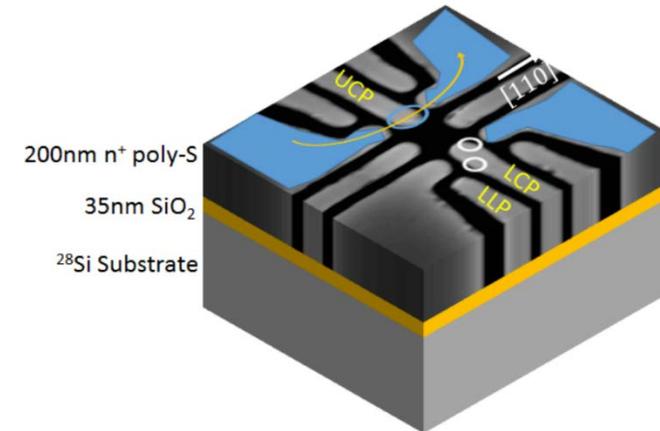
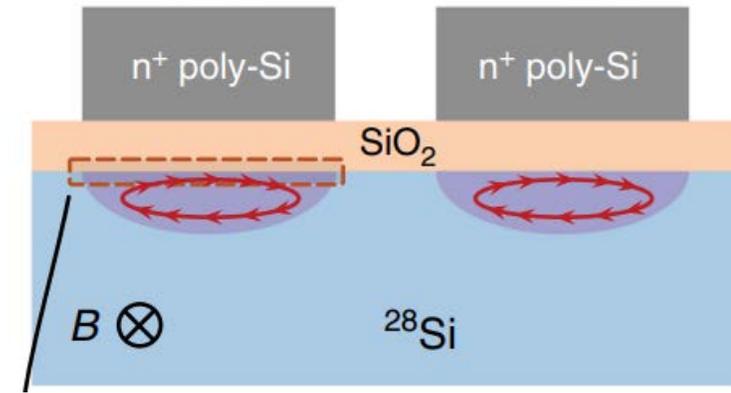
- Motivation
- Their system
- What they have done
  - Use g-factor difference from the SO coupling at the Si/SiO<sub>2</sub> interface to get second axis of control for DQD S-T qubit
  - Study qubit noise and SO interaction at interface
  - Quantitative characterization of charge noise in MOS qubit (quasi-static detuning variance and Hahn-echo time)
  - Demonstrate that MOS interfaces have inherent properties for two-axis qubit control
- Conclusion

# Motivation

- Persistent concerns about disordered Si/SiO<sub>2</sub> interface leading to
  - Additional charge noise
  - Variable g-factors
- Many have used Si/SiGe heterostructures to move interface away
  - Results in small and/or variable valley splitting
- Want a direct characterization of charge noise at MOS interface
- Means to characterize a SO S-T qubit and its coherent qubit rotations
- See full magnetic field angular dependence
- *Spend more time with spin qubits, particularly at Si interface to SiO<sub>2</sub>*

# The System

- Fully foundry-compatible process with single gate layer MOS poly-silicon gate stack on an epitaxially-enriched  $^{28}\text{Si}$  epilayer with 500 ppm residual  $^{29}\text{Si}$
- Hall bar measurements on same wafer yield
  - $n = 5.7 \times 10^{11} \text{ cm}^{-2}$
  - $\mu = 4500 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$
  - $V_{th} = 1.1 \text{ V}$
  - $T_e \sim 150 \text{ mK}$
- Accumulation mode using highly-doped n+ poly-silicon gates
- Tune lower half of device to form DQD (one tunnel-coupled to LRG)
- Upper half used as SET charge sensor

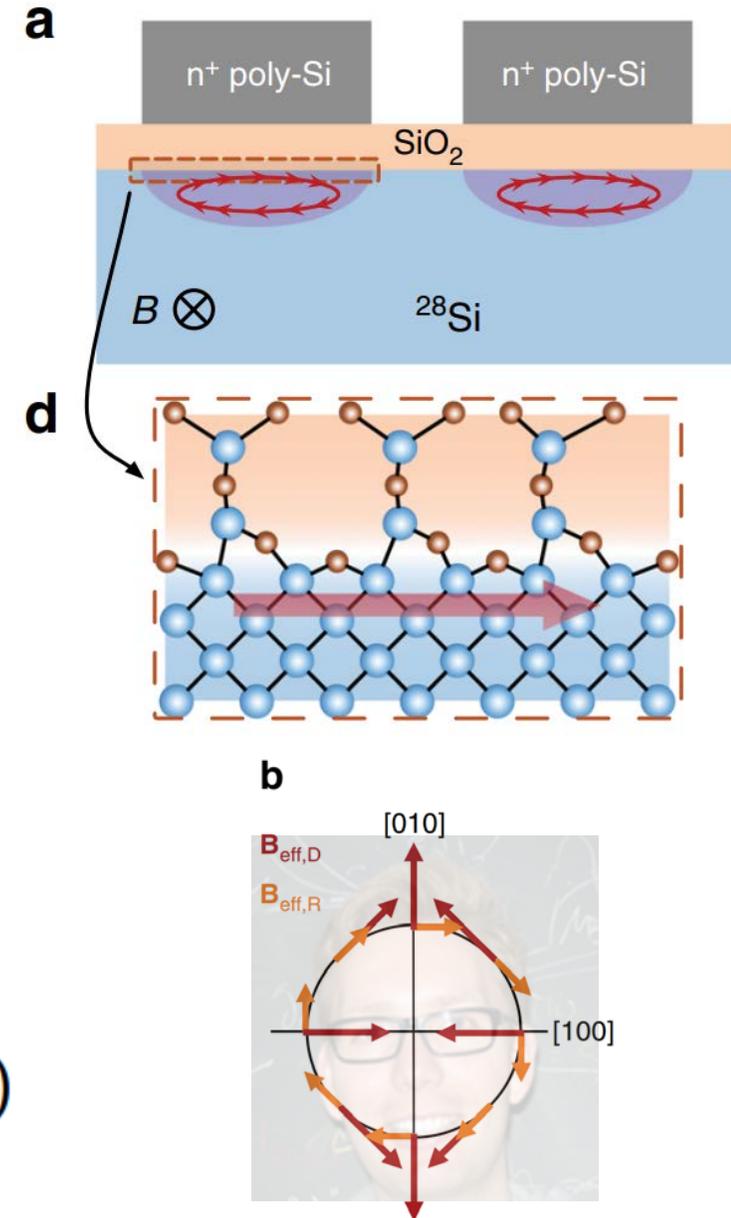


# Spin-Orbit Interaction

- Interface leads to SOI:
  - B field parallel to interface leads to cyclotron motion of electrons establishing net momentum along interface
  - Coupling of this momentum perpendicular to the electric field at the interface produces the SOI
- Rashba due to vertical electric potential at interface (structural inversion asymmetry)
- Dresselhaus due to microscopic interface inversion asymmetry (potentially variable interatomic fields)
- Not unique to this system
  - Analysis of interfacial effects on g-factor variability useful in other systems

$$H_R \propto \gamma_R (P_y \sigma_x - P_x \sigma_y)$$

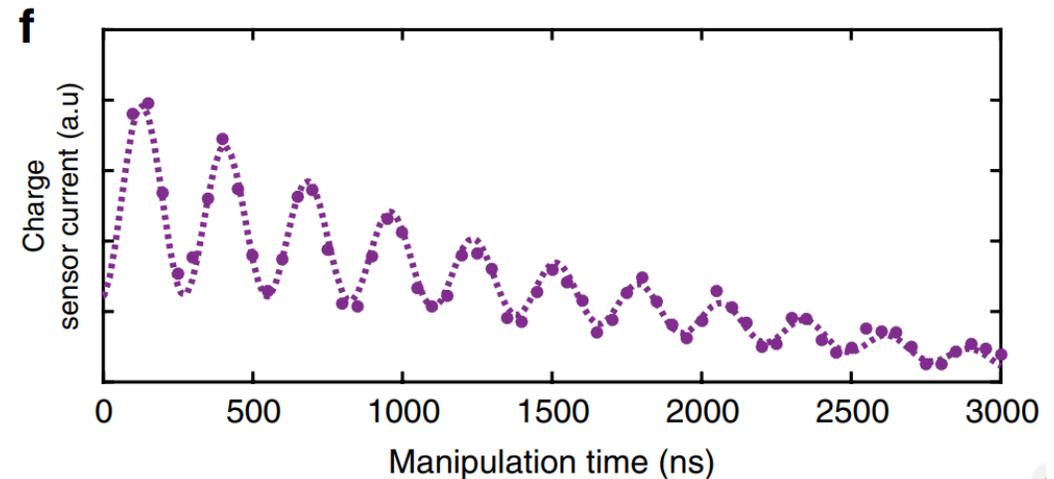
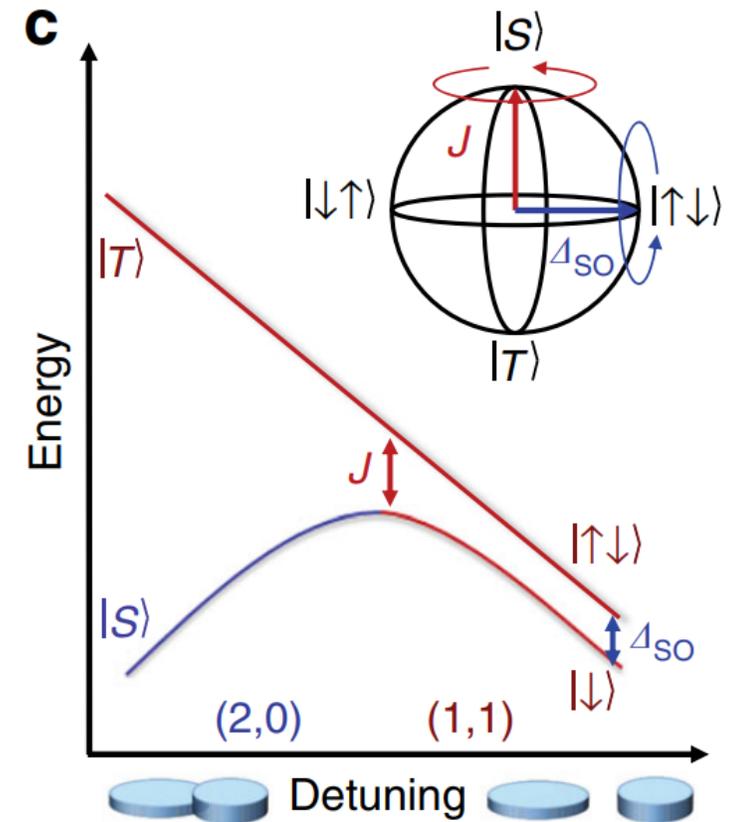
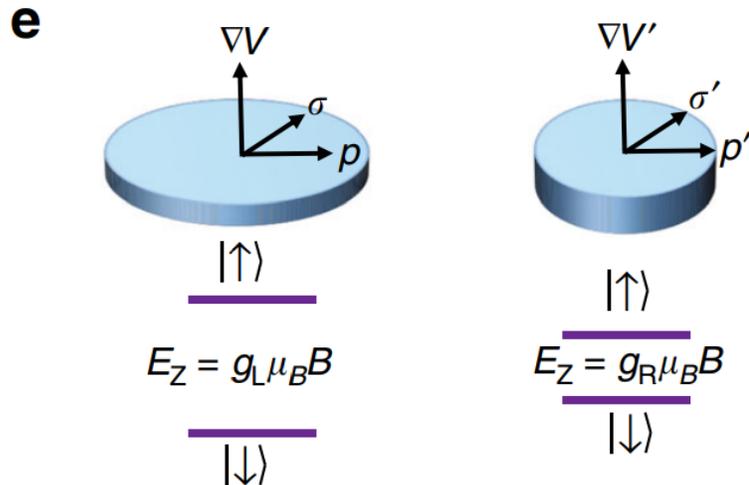
$$H_D \propto \gamma_D (P_x \sigma_x - P_y \sigma_y)$$



# Tuning the DQD

- Near zero detuning ( $\epsilon = 0$ ),  $J$  dominates  $\rightarrow$  rotations around Z-axis
- Deep into (1,1) charge sector ( $\epsilon > 0$ ),  $J$  small  $\rightarrow$  rotations around X-axis (different Zeeman energies for the two dots)
  - $\rightarrow$  use inherent g-factor difference at interface as second axis of control!

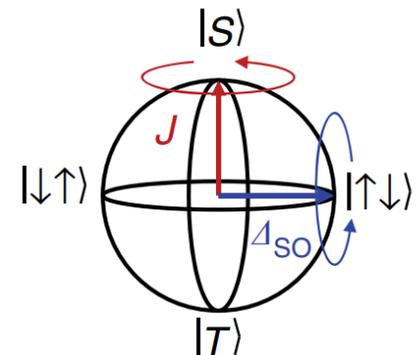
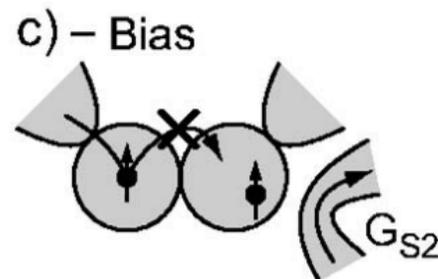
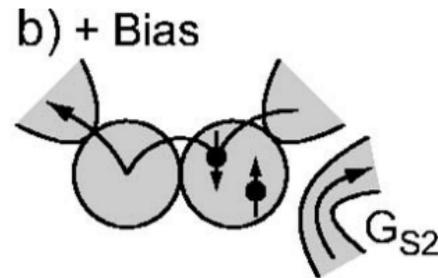
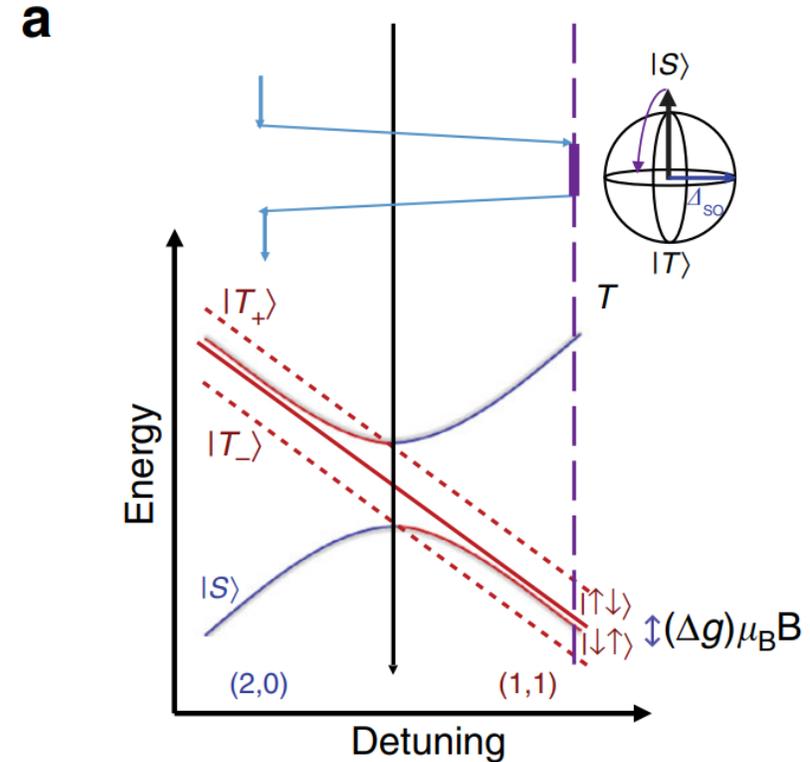
$$f(\epsilon) = \frac{1}{h} \sqrt{J(\epsilon)^2 + \Delta_{SO}^2}$$



# Operation of the S-T Qubit

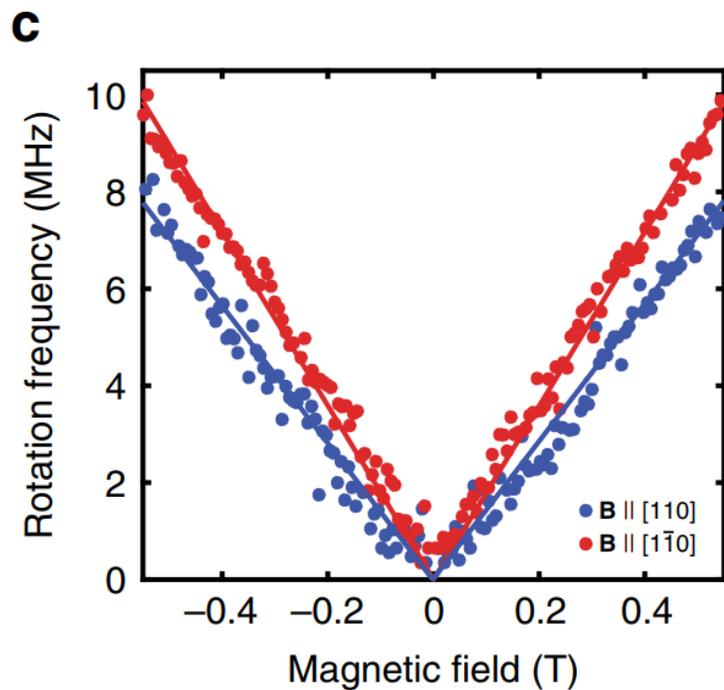
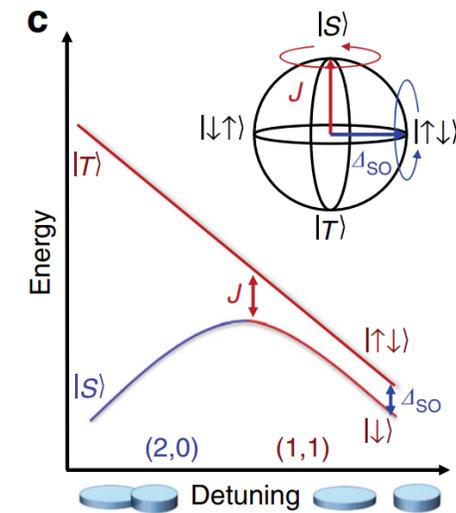
- Basis of eigenstates of the two-spin system in limit of large S-T exchange  $J$  ( $S$  &  $T_0$ )
- Small applied B-field splits off  $m = \pm 1$  triplet states by  $E_z = g\mu_B B$
- Initialize in  $(2,0)$
- Rapid adiabatic pulse to (deep)  $(1,1)$  state
- Difference in Larmor frequency yields rotations in X-axis between  $S(1,1)$  and  $T_0(1,1)$ 

$$2\pi f = \Delta\omega = \Delta g\mu_B B / \hbar$$
- Driving closer to the anticrossing lets  $J$  dominate and drives the Z-axis rotations
- Detection using Pauli spin blockade [1] and the remote charge sensor to determine if state passed through  $(2,0)$  or was blockaded in  $(1,1)$  during readout

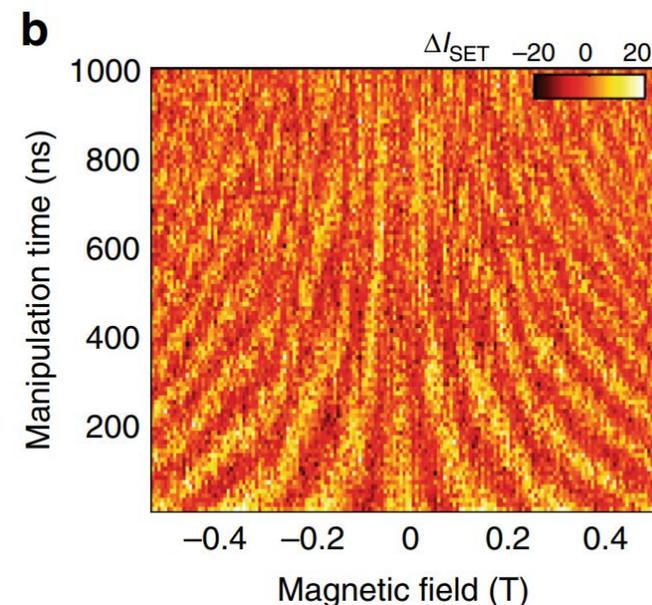


# Coherent Rotations

- Clear oscillations (X-axis) at large detuning to (1,1) manipulation point
- Difference in slopes indicative of angular dependence of  $\Delta g$ 
  - Qualitatively consistent with different SOI in each dot
- Extract  $\Delta\alpha = 1.89 \text{ MHzT}^{-1}$ ,  $\Delta\beta = 15.7 \text{ MHzT}^{-1}$



Charge sensor current as function of B field along  $[1-10]$  direction

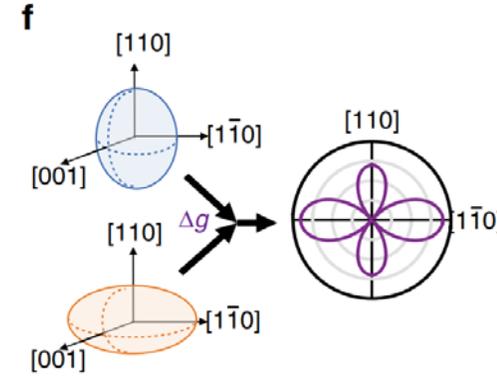
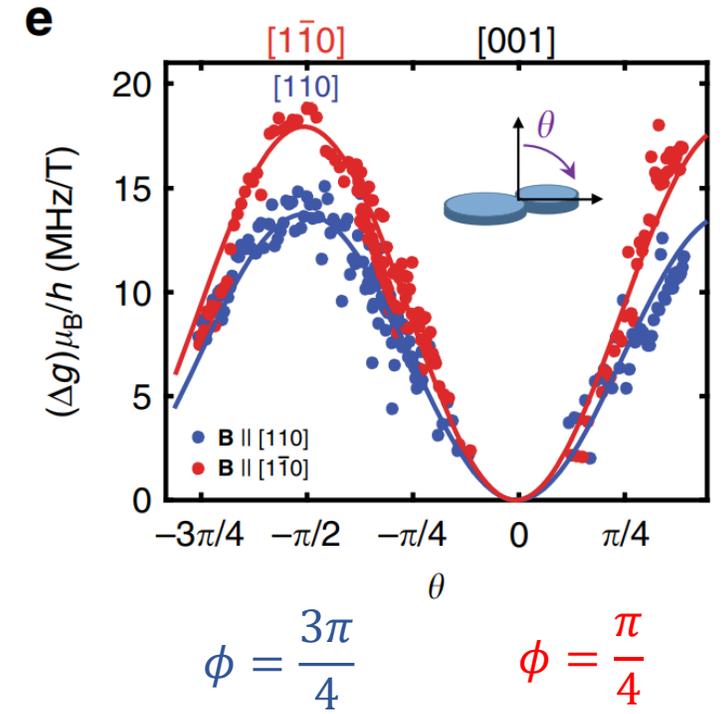
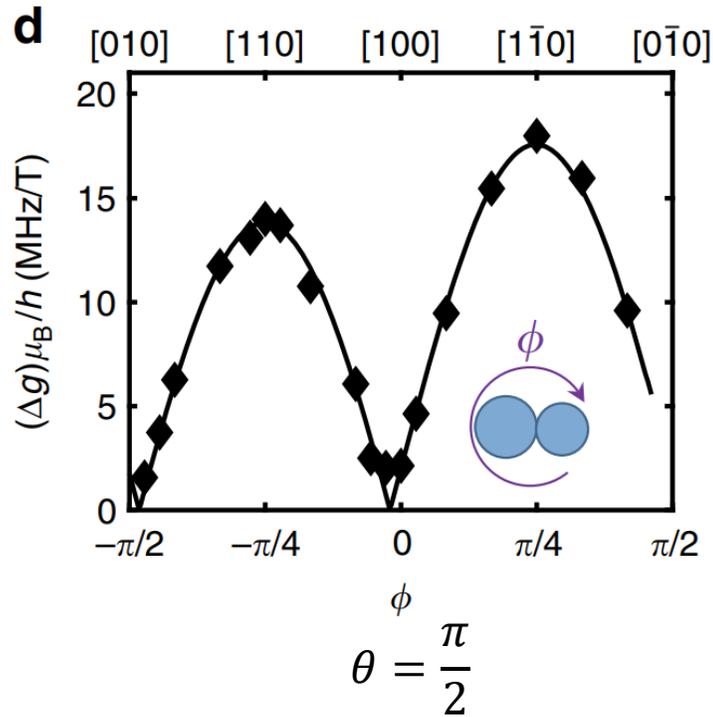
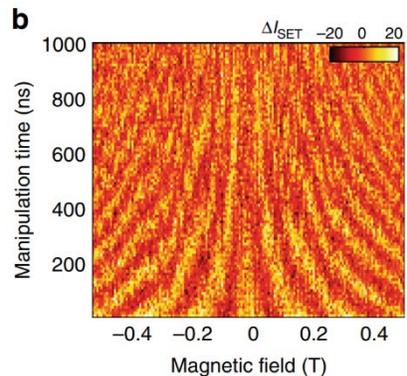


# B-Field Dependence

- Choice of B-field direction utilized to maximize SOI to drive spin rotations, or cancel them out
  - Potentially important for uniform spin-splitting between multiple QDs in devices
- Out-of-plane field with respect to [001] ( $\theta$ ) suppresses SOI difference
- In-plane field with respect to [100] ( $\phi$ ) can maximize SOI difference

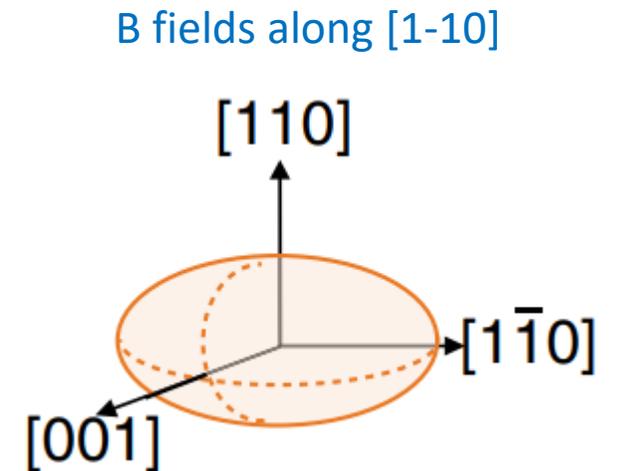
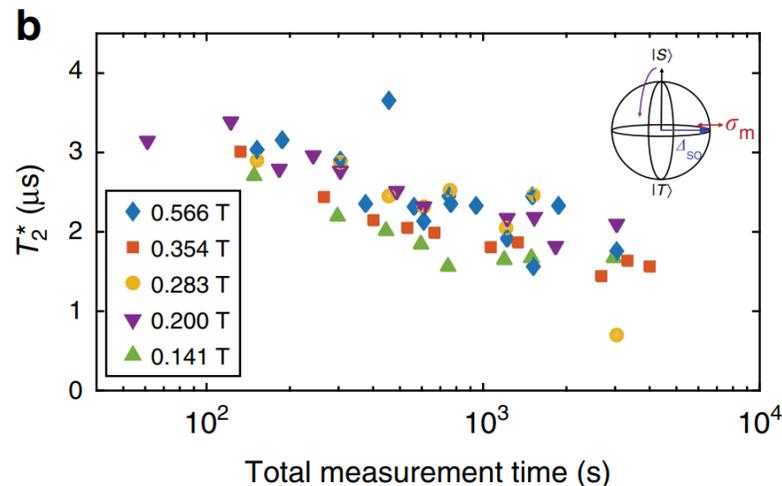
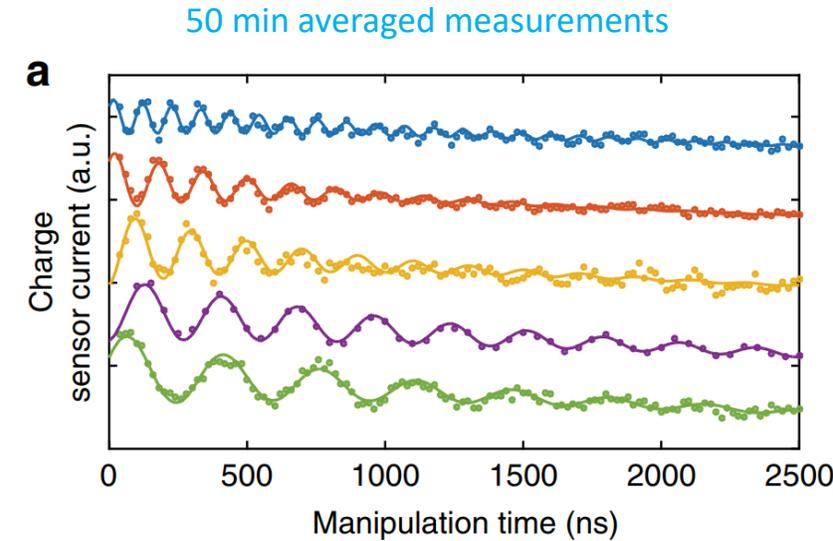
$$\begin{aligned}
 f_{\text{rot}}(\theta, \phi) &= \Delta_{\text{SO}}(\theta, \phi)/h \\
 &= (\Delta g(\theta, \phi))\mu_B B/h \\
 &= \frac{2}{h} |\langle S|H|T_0 \rangle| \\
 &= |\mathbf{B}| \underbrace{|\Delta\alpha - \Delta\beta \sin(2\phi)|}_{\text{Difference in Rashba and Dresselhaus } g\text{-tensor perturbations between two QDs}} \sin^2(\theta)
 \end{aligned}$$

*Difference in Rashba and Dresselhaus g-tensor perturbations between two QDs*



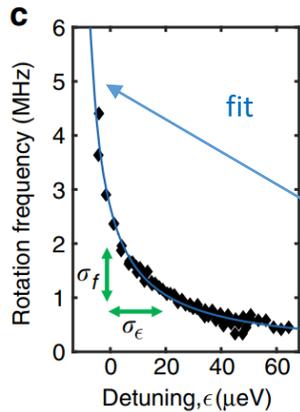
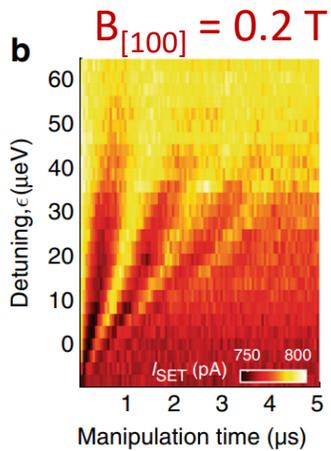
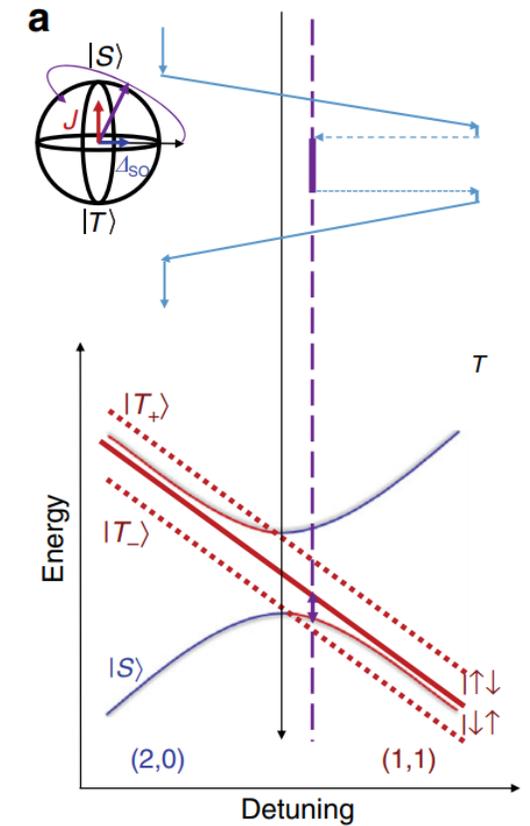
# Timescales

- Nuclear spin flips (background  $^{29}\text{Si}$ ) lead to time-variation of Overhauser field, which results in decay in time of coherent oscillations (*here: X-axis*).
- Decay in oscillation amplitude fits a Gaussian consistent with quasi-static noise
  - $T_2^* = 1.6 \mu\text{s}$  extracted for long-averaging timescales assuming decay like  $\exp[-(t/T_2^*)^2]$
- Relative absence of B-field dependence suggestive that the interface SOI doesn't contribute to  $T_2^*$   $\rightarrow$  no additional noise due to MOS interface (consistent with bulk  $^{29}\text{Si}$ )



# Charge Noise Characterization

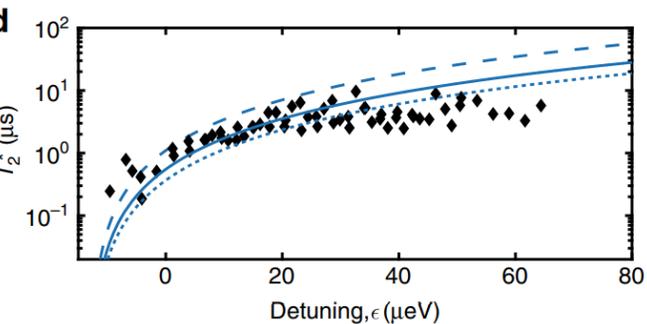
- Initialize in  $S(0,2)$  state then drive to  $S(1,1)$  near  $J(\epsilon) \approx 0$ , then drive to and from  $J(\epsilon)$  around  $\epsilon = 0$  for a waiting time, rotating qubit around Bloch sphere
- Associate saturation of  $T_2^*$  at deep detuning with dominant noise mechanism going from charge noise on the confinement gates to magnetic noise due to residual  $^{29}\text{Si}$



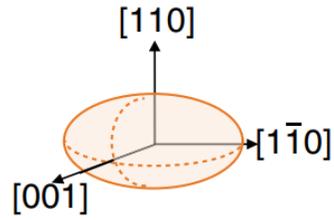
$$\sqrt{J(\epsilon)^2 + \Delta_{SO}^2}$$

$$J(\epsilon) \propto \epsilon^{-1}$$

Fit rotation frequency to  $\frac{df(\epsilon)}{d\epsilon}$ , then the ratio of  $T_2^*$  to  $|df(\epsilon)/d\epsilon|^{-1}$  gives rms charge noise [1] of  $\sigma_\epsilon = 2 \pm 0.6 \mu\text{eV}$



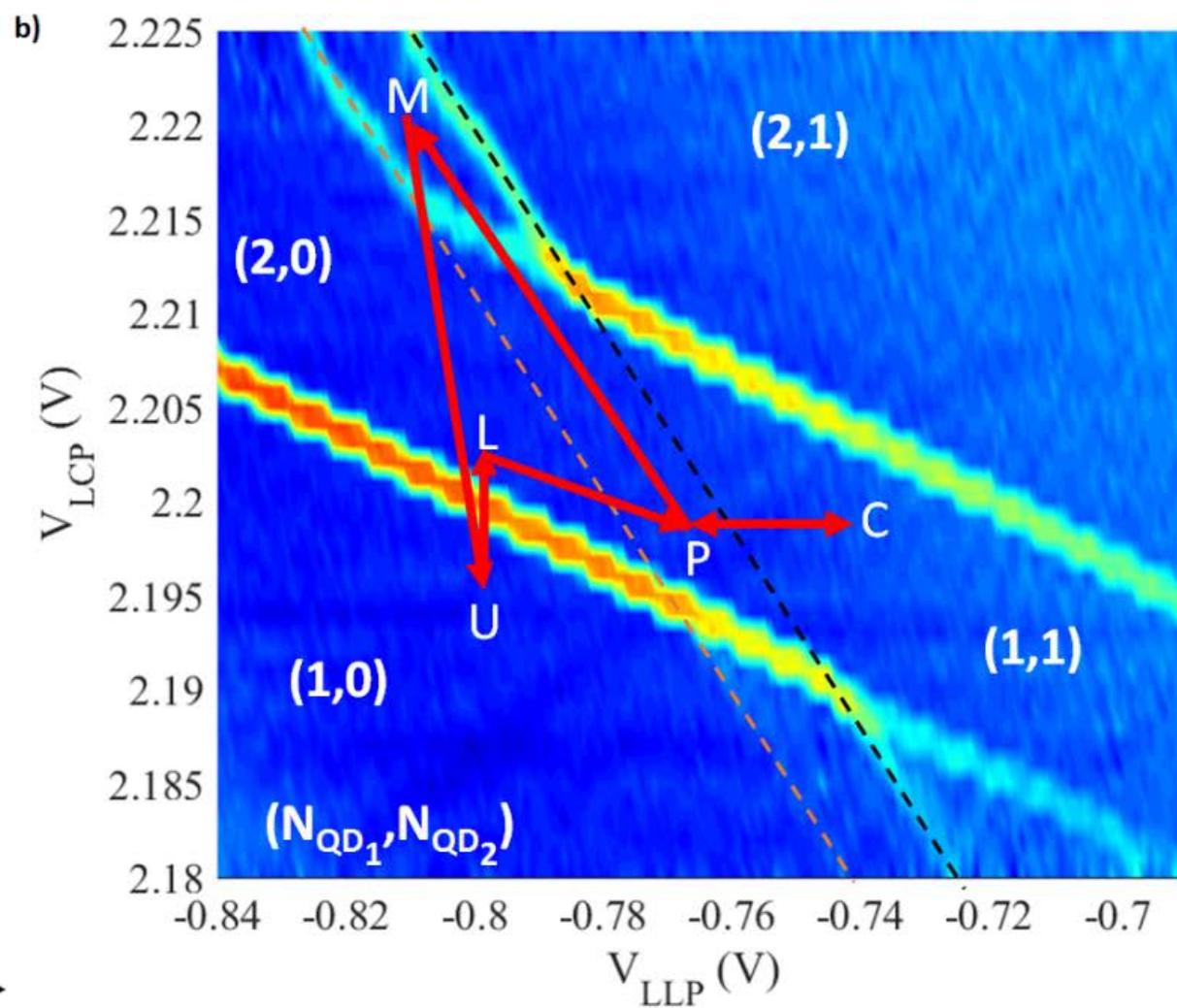
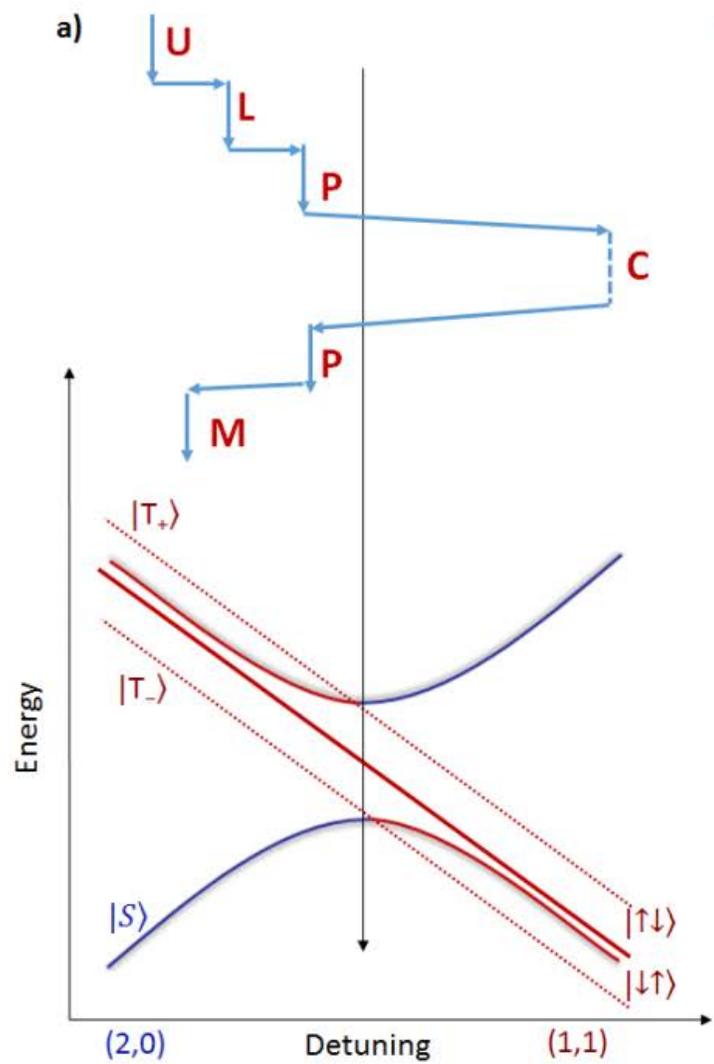
$$T_2^* = \frac{1}{\sqrt{2}\pi\sigma_\epsilon} \left| \frac{df}{d\epsilon} \right|^{-1}$$



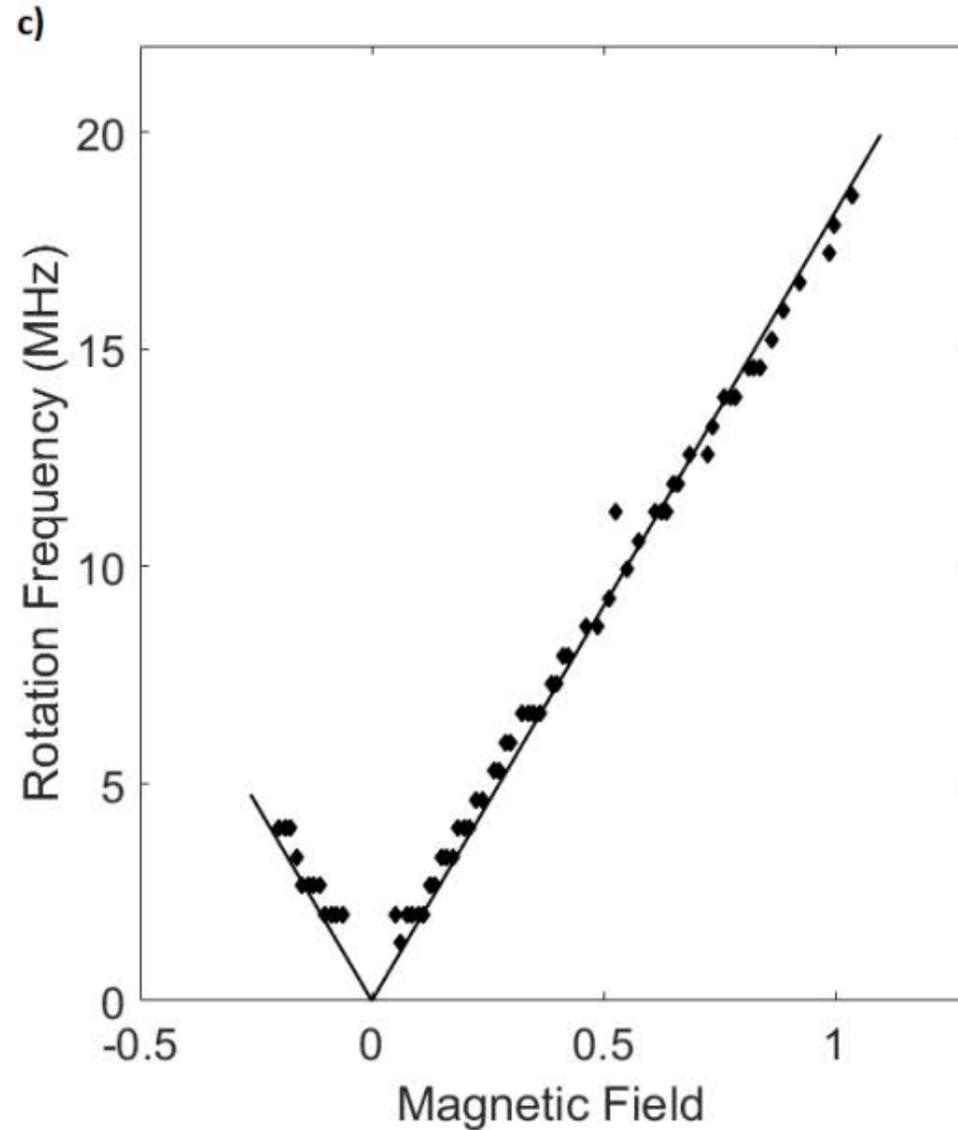
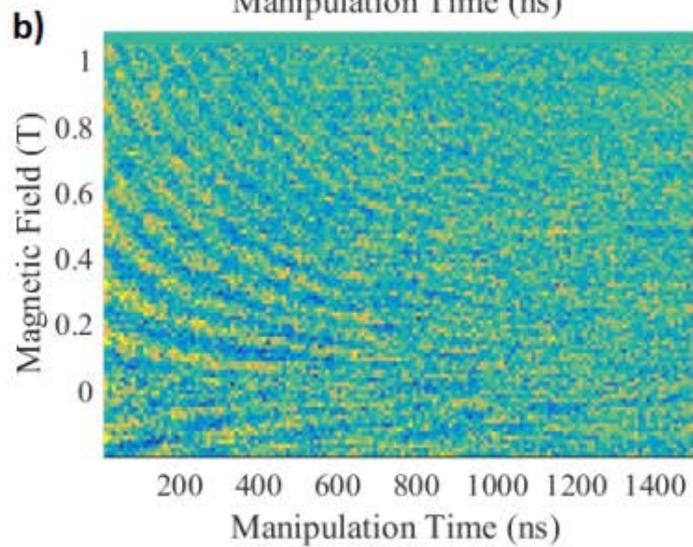
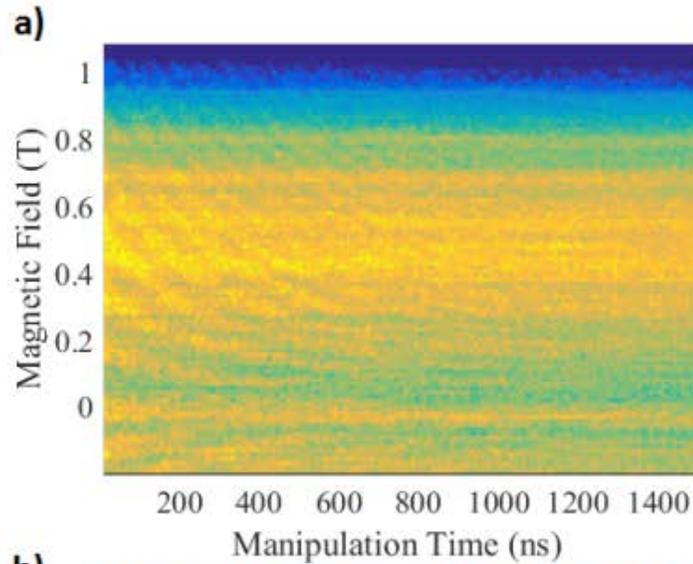
# Conclusion

- All-electrical two-axis control of MOS DQD using the intrinsic details of the system at the interface
  - Exploits interfacial SOI + detuning for two axis control
- Charge noise characterized at the interface
- $T_2^*$  comparable to other systems (Ga/AlGaAs ; Si/SiGe)

Thanks for listening!



$$I_{SET} = A \sin(2\pi ft + \phi_0) \exp[-(t/T_2^*)^2] + Bt + C$$



At (1,1) manipulation point

